

10keV RHEED Electron Source



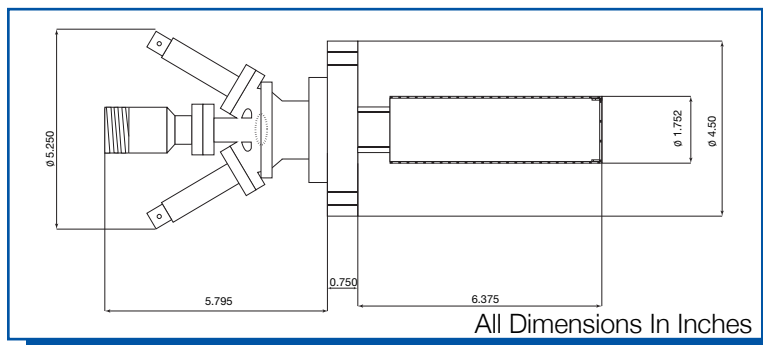
Features

- Magnetically Shielded Optics
- 2¾" or 4½" CFF Mounting Flange

Description

Reflection High-Energy Electron Diffraction (RHEED) is an integral part of the MBE process. In thin film deposition RHEED provides important information for the user. First, its RHEED pattern conveys specific information about the surface, and second its intensity oscillation provides quantitative measures of the growth rate. RH-10 kV RHEED Electron Source is designed for operation in an UHV environment at beam voltage up to 10 kV. The 10 keV RHEED system provides a precision focus and well defined diffraction patterns with high screen intensity. The electron optics are magnetically shielded for improved operation.

Real-time RHEED patterns are captured with the optional RHEED Image Analysis hardware and software system that gives the user the power to grow high quality thin films. A complete system includes the 10 keV RHEED Electron Source, Power Supply, and Cable Set.



Models	Description
RH-10kV	10 KeV Electron Source
RH-10VPS	Power Supply
RH-CBL	Cable Set

Specifications

Beam Voltage	10 kV
Filament Current	3 A
Emission Current	5 A
Mounting Flange	4½" CF
Spot Size	1.0 mm at 17"
Maximum Bake out Temperature	230 °C

